EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S79	2	(("6027669") or ("6126518")).PN.	US-PGPUB; USPAT	OR	OFF	2006/04/04 11:31
S80	6	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) near2 (silica or silicon dioxide or SiO".sub.2")	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 11:35
S81	0	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not S80	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 11:38
S82	16	(mask or photomask or reticle) same glass same (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not S80 not S81	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 11:40
S83	2523	((mask or photomask or reticle) near3 (phase or shift$3 or reflect$3 or extreme ultraviolet or extreme UV or EUV) or PSM) same glass not S80 not S81 not S82	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 11:41
S84	89	S83 and glass same (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 11:43
S85	139	S83 and glass same (polish$3 or abra$4 or grind$3) not S84	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 11:45
S86	7916	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 11:46
S87	1884	S86 and (mask or photomask or reticle) same glass same (blank or base or substrate) not S80 not S82 not S84 not S85	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 11:59
S88	674	S83 and S86	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 11:59

S89	6	S88 and (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or SiO$6) not S80 not S82 not S84 not S85	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:01
S90	8528	451/36,37,41,42,390.ccls. or 65/60.1,61.ccls. or 427/160,165,290,292.ccls.	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:12
S91	593	S90 and (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6) not S80 not S82 not S84 not S85 not S89	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:14
S92	503	S91 and (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:15
S93	3	S92 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 21:08
S94	429	S92 and (polish$3 or abra$4 or grind$3) same (pressure or force or load) not S93	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:18
S95	57	S94 and (pressure or force or load) same glass	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:19
S96	1388	51/308.ccls. not S80 not S82 not S84 not S85 not S89 not S93 not S95	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:24
S97	2	S96 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:27
S98	3	S96 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) not S97	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:28
S99	73	S96 and hydroly$4 with (silica or silicon dioxide or SiO".sub.2" or SiO$6) not S97 not S98	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:29

S10 0	6	S99 and hydroly$4 same (silicon or Si) with (organic or polymer) not S97 not S98	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:31
S10 1	3	S99 and hydroly$4 same (silicon or Si) same (organic or polymer) not S100	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:32
S10 2	13	(Kesahiro near2 Koike or Junji near2 Miyagaki).in. not S80 not S82 not S84 not S85 not S89 not S93 not S95 not S97 not S98 not S100 not S101	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 12:35
S10 3	1096	(polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") same (alkali metal or sodium or potassium or "Na" or "K") not S80 not S82 not S84 not S85 not S89 not S93 not S95 not S97 not S98 not S100 not S101 not S102	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 13:39
S10 4	85	S103 and 51/308.ccls. and (colloid$2) same (silica or silicon dioxide or SiO".sub.2") same (alkali metal or sodium or potassium or "Na" or "K")	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 13:42
S10 5	21	S104 and (alkali metal or sodium or potassium or "Na" or "K") same impur$5	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 13:43
S10 6	5	(glass and (mask or photomask or reticle) and (blank or substrate) and (polish$3 or abra$4 or grind$3) and (colloid$2) and (silica or silicon dioxide or SiO".sub.2") and ("pH" or (protru$4 or bulg$3 or project$3 or bump$3))).clm. not S80 not S82 not S84 not S85 not S89 not S93 not S95 not S97 not S98 not S100 not S101 not S102 not S105	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 13:47
S10 7	777	430/4.ccls.	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 13:47

S10 8	1	(S86 or S107) and (mask or photomask or reticle) same glass same (blank or substrate) same (polish$3 or abra$4 or grind$3) same ("pH" or (protru$4 or bulg$3 or project$3 or bump$3)) not S80 not S82 not S84 not S85 not S89 not S93 not S95 not S97 not S98 not S100 not S101 not S102 not S105 not S106	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 13:50
S10 9	5	(mask or photomask or reticle) same glass same (blank or substrate) same (polish$3 or abra$4 or grind$3) same "pH" not S80 not S82 not S84 not S85 not S89 not S93 not S95 not S97 not S98 not S100 not S101 not S102 not S105 not S106 not S108	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 14:00
S11 0	1732812	glass	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:21
S11 1	345551	polish or polishing or polished	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:22
S11 2	574655	silica	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:23
S11 3	22006	S110 and S111 and S112	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:24
S11 4	1241486	pH	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:24

S11 5	6704	S113 and S114	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:25
S11 6	8523	S114 same S111	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:25
S11 7	1767	S116 and S110 and S112	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:27
S11 8	45107	S110 same S111	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:35
S11 9	1069	S117 and S118	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:35
S12 0	3307	S111 near10 S114	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:36
S12 1	613	S120 and S119	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:37
S12 2	40088	colloidal silica	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:38

S12 3	283	S122 and S121	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:38
S12 4	652622	glass.ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:39
S12 5	128049	S111.ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:41
S12 6	156105	S112.ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:42
S12 7	491	S124 and S125 and S126	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:42
S12 8	13	S127 and S123	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 14:45
S12 9	9	S128 not S80 not S82 not S84 not S85 not S89 not S93 not S95 not S97 not S98 not S100 not S101 not S102 not S105 not S106 not S108 not S109	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 15:33
S13 0	70	S111 same S122 same S110 same (silicon dioxide or SiO".sub.2") not S80 not S82 not S84 not S85 not S89 not S93 not S95 not S97 not S98 not S100 not S101 not S102 not S105 not S106 not S108 not S109 not S129	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 16:59

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S13 1	8423	S111 same S114 not S80 not S82 not S84 not S85 not S89 not S93 not S95 not S97 not S98 not S100 not S101 not S102 not S105 not S106 not S108 not S109 not S129	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 17:12
S13 2	9	S130 and S131	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/04 18:24
S13 3	92	S90 and (colloidal silica same (polish or polishing or polished) same "pH") not S80 not S82 not S84 not S85 not S89 not S93 not S95 not S97 not S98 not S100 not S101 not S102 not S105 not S106 not S108 not S109 not S129 not S132	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 19:51
S13 4	1	S133 and (colloidal silica same (polish or polishing or polished) same "pH") same glass	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2006/04/04 20:14
S13 5	18154	(quartz near3 glass) with (mask or photomask or reticle or substrate or blank or support)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 10:42
S13 6	6013	(mask or photomask or reticle) with (polish$6 or lap$6)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 10:45
S13 7	73	S135 and S136 and excimer	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 10:44
S13 8	3447938	(mask or photomask or reticle or substrate or blank or support)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 10:46
S13 9	1142	S138 and ((pressure or weight$6 or load) with ("kg/cm.sup.2" or "g/cm.sup.2")) same (polish$6 or lap$6)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:28
S14 0	37148	(polish$6 or lap$6) same (quartz or glass)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 10:57
S14 1	426	S139 and S140	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 10:58
S14 2	36882	colloid$6 near5 (silica or "SiO.sub.2")	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 10:59

S14 3	1597	hydroly$6 with S142	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:01
S14 4	159	S141 and S142	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:02
S14 5	146	S139 and S142 not S144	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:05
S14 6	4	S137 and S142	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:22
S14 7	46	S137	USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:26
S14 8	305	S139 and S142	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:26
S14 9	159	S148 and S140	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:27
S15 0	218	(glass or quartz) same ((((pressure or weight$6 or load) with ("kg/cm. sup.2" or "g/cm.sup.2")) same (polish$6 or lap$6))	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:29
S15 1	46	S150 and S142	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/05/03 11:30